IN THE SPECIFICATION:

Please amend the specification by replacing paragraphs as follows:

A. Specification Paragraphs With Mark-ups to Show Changes Made

The following are mark-ups to show changes made to paragraph 92 starting at page 32, line 2 and ending at page 33, line 8:

[92] According to the methods and apparatus of the invention, the wavelength of the laser energy, the pulse length and shape of the laser energy, the laser energy density, the laser beam size and/or shape, the laser irradiation geometry, the ambient conditions, the amount and disposition of the energy transfer medium and/or the composition of the energy transfer medium are precisely and selectively controlled. The exact parameters may be calculated for the specific application and environment, including consideration of the optical constraints of the materials and the size of the particles. The wavelength of the laser should be chosen to target either the particle, substrate, the ETM ~~of~~ or some combination thereof. The energy density should be above the removal threshold but below the damage threshold. Further, the energy density should be sufficient to be absorbed by the particle, the substrate, or the energy transfer medium, either directly or by conduction from the sample or substrate, or some combination thereof. The pulse length of the laser is preferably sufficiently short in order to achieve the desired temperature distribution of the energy transfer medium, but not any shorter in order to decrease the likelihood of substrate damage. The laser beam shape and/or size is preferably as large as possible to clean as large an area as possible. Ideally, the laser beam is a uniformly

intense beam. The irradiation geometry is chosen to optimize the energy transfer to the ETM and minimize substrate or device damage. The energy transfer medium is preferably capable of providing sufficient kinetic energy to the particle in order to remove the particle during the explosive evaporation of the energy transfer medium. The energy transfer medium may be introduced as a uniform layer of a particular thickness onto the substrate, may be introduced so as to be condensed only in the capillary spaces under the particle, or any combination thereof, the exact selection being dependent on the substrate/particle system being used. Additionally, the composition of the energy transfer medium may be selected such that it will couple more efficiently to the laser being used.

G1

The following are mark-ups to show changes made to paragraph 117 starting at page 44, lines 1-5:

[117] Patterns of particle(s) deposited by a laser particle gun can be achieved by placing the substrate 220 close to the target substrate 240 and irradiating the substrate 220 with a uniform intensity laser beam focused through a mask in photolithography, or by overlapping small focused beams. This is similar in concept to laser induced forward transfer ~~(LIST)~~ (LIFT) for generating thin film material patterns.

G2